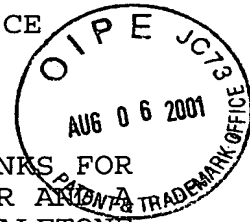


PATENT APPLICATION  
IN THE U.S. PATENT AND TRADEMARK OFFICE

August 3, 2001

Applicant(s): Toshiaki MOTONAGA et al.

For: HALFTONE PHASE SHIFTING PHOTOMASK AND BLANKS FOR  
HALFTONE PHASE SHIFTING PHOTOMASK THEREFOR AND A  
METHOD FOR FORMING PATTERN BY USING THE HALFTONE  
PHASE SHIFTING PHOTOMASK



Serial No.: 09/825 578                      Group: 2622  
Filed: April 3, 2001                      Examiner: Unknown  
International Application No.: N/A  
International Filing Date: N/A  
Atty. Docket No.: OPS Case 529

Assistant Commissioner for Patents  
Washington, DC 20231

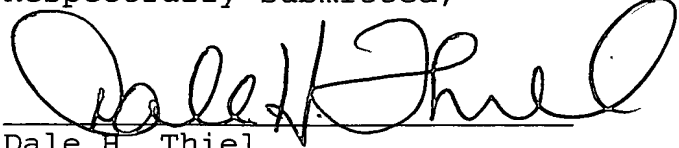
INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the provisions of Rules 1.97(b)(1) and 1.98, enclosed and listed on Form PTO-1449 are the references discussed on pages 1-4 of the application. Also enclosed and listed on Form PTO-1449 are two English-language references corresponding to Japanese Patent No. 58-173744 which is discussed on page 1 of the application.

Further consideration of the application is respectfully solicited.

Respectfully submitted,

  
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Reg. No. 36 589  
Reg. No. 31 257  
Reg. No. 24 949  
Reg. No. 40 694  
Reg. No. 36 328  
Reg. No. 44 621

Encl: Form PTO-1449 and one copy of each listed reference